Shape transition of coherent three-dimensional (In,Ga)As islands on GaAs(100)

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The shape transition of coherent three-dimensional (3D) islands is observed experimentally in the (In,Ga)As/GaAs(100) material system. In the molecular-beam epitaxy of a 1.8-nm-thick In0.35Ga0.65As single layer, we find that the shape of the coherent 3D islands transforms from round to elongated when increasing the growth temperature. A quantitative agreement of our experimental data with the theoretical work of Tersoff and Tromp is achieved. © 2001 American Institute of Physics [DOI: 10.1063/1.1428107]

For Stranski–Krstanov systems, uniform two-dimensional (2D) layers can relax by undergoing a morphological change of the surface profile without generating dislocations. 1-2 This strain-induced morphological instability results in the formation of coherent three-dimensional (3D) islands whose shape is usually isotropic or elongated. There has been great interest in the shape of these islands for the direct synthesis of quantum dot and quantum wire structures which have unique applications for novel optoelectronic devices. We have recently demonstrated formation of a quantum wire structure based on elongated islands in the (In,Ga)As/GaAs(100) material system. 3 On the other hand, Tersoff and Tromp 4 predicted that a shape transition should occur for 3D islands if the growth of the island height is kinetically limited. Subsequent theoretical work has shown that such a shape transition is a common feature for both 3D 5 and 2D 6,7 islands, which was confirmed for CoSi2 on Si(100). 8 However, to the best of our knowledge, the shape transition has so far not been reported experimentally in III–V semiconductor systems. Moreover, experimental routes to reproducibly realize the shape transition are technologically important.

In this letter, we demonstrate the shape transition of 3D (In,Ga)As islands grown on GaAs(100) by molecular-beam epitaxy. For 1.8-nm-thick (In,Ga)As single layers, we show that the formation of 3D islands is a kinetically limited process. The shape transition is realized by changing the growth temperature. A good agreement is obtained between our experimental data and the theoretical work of Tersoff and Tromp. 4

Three 1.8-nm-thick (In,Ga)As single-layer samples were grown on GaAs (100) substrates with miscut smaller than 0.05° at temperatures of 540, 475, and 430 °C. After the native oxide was desorbed from the GaAs substrate surface at 580 °C, a 110-nm-thick GaAs buffer layer was grown before the substrate was cooled down to the temperature for (In,Ga)As deposition. The In mole fraction was calibrated by x-ray diffraction of an (In,Ga)As/GaAs superlattice sample grown continuously at 540 °C. The In mole fraction is 0.35 and the As4 to Ga flux ratio is about 5. The growth rate of GaAs and In0.35Ga0.65As is 0.235 and 0.3615 μm/h, respectively. Characterization of the surface morphology was performed by atomic force microscopy (AFM) in contact mode in air with a 75 μm scanner.

Figures 1(a), 1(b), and 1(c) depict the AFM top views of the In0.35Ga0.65As single-layer samples grown at temperatures of 540, 475, and 430 °C, respectively, revealing the formation of 3D islands. At relatively low growth temperatures [Figs. 1(b) and 1(c)], round-shaped islands are observed, whose size increases with increasing the growth temperature. The average island diameters are about 28 nm [Fig. 1(b)] and 18 nm [Fig. 1(c)], respectively. In contrast, at 540 °C [Fig. 1(a)], the islands are elongated. For most islands, the length to width ratio is about 6 with the island width of about 40 nm. This demonstrates that, for fixed In mole fraction and layer thickness, the size and, most importantly, the shape of these dislocation-free islands (see Ref. 3) are varied by solely changing the growth temperature. Since the growth temperature directly governs the surface diffusion length, this is a first indication that the formation of these coherent In0.35Ga0.65As islands is a kinetically limited process. 9 To compare, we grew a 1.8-nm-thick (In,Ga)As single-layer sample with larger In mole fraction of 0.45 at 540 °C. The AFM image [Fig. 3(a)] of this sample reveals almost round-shaped islands. Thus, for a certain growth temperature, the shape of the 3D islands is observed experimentally in the (In,Ga)As/GaAs(100) material system. In the molecular-beam epitaxy of a 1.8-nm-thick In0.35Ga0.65As single layer, we find that the shape of the coherent 3D islands transforms from round to elongated when increasing the growth temperature. A quantitative agreement of our experimental data with the theoretical work of Tersoff and Tromp is achieved. © 2001 American Institute of Physics [DOI: 10.1063/1.1428107]

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Correspondingly, the growth of a 1.8-nm-thick InGaaS layer at substrate temperatures of 540 °C, 475 °C, and 340 °C. The observation is along the [011] azimuth from a window set at the background. The inset shows the same curves with low magnification.

temperature, the shape of the islands is also determined by the In mole fraction with larger In mole fraction (strain) favoring isotropic islands.

The evolution of the InGaaS layers for the three samples was monitored in situ by reflection high-energy electron diffraction (RHEED) with the incident electron beam along [011]. Figures 2(a), 2(b), and 2(c) depict the RHEED intensity taken from a window set in the background during deposition of the InGaaS layers grown at 540, 475, and 340 °C, respectively, i.e., corresponding to the samples with the surface morphologies shown in Figs. 1(a), 1(b), and 1(c). The RHEED intensity oscillations in the initial deposition stage reveal layer-by-layer growth until about one monolayer where the island energy per unit volume can be written as

\[
\frac{E}{V} = 2\Gamma \left( \frac{1}{s} + \frac{1}{t} \right) \delta c h \left[ \frac{1}{s} \ln \left( \frac{s}{\phi h} \right) + \frac{1}{t} \ln \left( \frac{t}{\phi h} \right) \right].
\]

where \(E\) denotes the island energy, \(s\), \(t\), and \(h\) the width, length, and height of the island, respectively, and \(V = hst\) the island volume. \(\theta\) is the contact angle; \(\Gamma = \gamma_{s} \csc \theta - \gamma_{c} \cot \theta\) with \(\gamma_{s}\) and \(\gamma_{c}\) the surface free energy per unit area of the edge facet of the island and of the substrate, respectively. \(c = \sigma_{s}^{*}(1 - \nu)/2\pi\mu\), where \(\nu\) and \(\mu\) are the Poisson ratio and the shear modulus of the substrate. \(\phi = e^{-\alpha_{s}^{{*}} \csc \theta}\), and \(\sigma_{s}\) is the bulk stress of the island. Corresponding to the thermodynamic limit, \(\gamma_{s}\) minimization of the energy per unit volume \(E/V\) with respect to the island width \(s\) and length \(t\) by optimizing the volume of the island results in \(s = t = a_{0} = e\varphi h e^{1/\gamma_{c}}\), i.e., square-shaped islands. In contrast, for a kinetically limited process with constant island height \(h\) which we show to apply for our experimental situation, minimization of the energy per unit volume \(E/V\) with respect to the island shape for fixed island volume gives \(s = t\), provided the area of the island is smaller than \(e_{a}a_{0}\). For larger area, the island becomes elongated. This corresponds to the case where the adatom diffusion length is small enough that migration between islands can be neglected and deposited material only attaches to the nearest island. The island will then grow without bounds and, for a certain island volume, the island shape is determined by Eq. (1). Hence, when the island becomes large enough, the optimal trade-off between surface energy and strain energy causes transformation into elongated shape. The solid line in Fig. 4 shows the width and length of the island as a function of its area according to Eq. (1). The bifurcation point in Fig. 4 corresponds to the island area of \((ea_{0})^{2}\) beyond which the island shape becomes elongated.

Good agreement between the theory and our experimental data is obtained for \(a_{0} = 280\,\text{Å}\). For the calculation, the island height \(h\) of 1.8 nm and the contact angle \(\theta\) of 9.3°, are determined from AFM line scans. The appropriate reference for \(\gamma_{s}\) for the Stranski–Kranzstrom growth mode is that of the wetting layer. Thus, we use \(\gamma_{s} = 57\,\text{meV/Å}^{2}\) and \(\gamma_{c} = 57\,\text{meV/Å}^{2}\) (see the following). The elastic moduli of InGaaS of \(C_{11} = 10.592 \times 10^{11}\,\text{dyn/cm}^{2}\) and \(C_{12} = 5.042 \times 10^{11}\,\text{dyn/cm}^{2}\) are obtained by interpolating between the data for GaAs and InAs according to the In mole fraction. As a result, we get \(\Gamma = 4.63\,\text{meV/Å}^{2}\) and \(a_{0} = 281.4\,\text{Å}\). The closed circles in Fig. 4 correspond to the experimental data determined from Fig. 1. Larger islands could not be obtained for the present In mole fraction and...
(In,Ga)As layer thickness due to In desorption upon further increase of the growth temperature.

Several important features should be considered when comparing the model with our experimental findings. First, the island height $h$ is to be kept constant. In our approach, we realize the shape transition by deposition of a constant number of monolayers of material at different growth temperatures. In principle, coherent 3D strained islands can lower their strain energy by increasing their height. However, as discussed previously, if the increase in height is kinetically limited, the island grows only laterally, i.e., the island height grows much slower than the width and shape transition occurs. Indeed, from the AFM images [Figs. 1(a)–1(c)], the average height of the islands corresponding to the samples grown at different temperatures is relatively constant. Even at 540 °C, which is closer to thermal equilibrium, the island height only slightly increases, which is the key point for understanding the observed shape transition. Second, the surface free energy of (In,Ga)As for arbitrary In composition is not well documented in the literature. Therefore, the values for the calculation are estimated from a linear interpolation between the data for GaAs(100) and InAs(100) which are, respectively, 65 and 44 meV/Å² according to Refs. 14 and 15. Finally, the values of $\gamma_e$ and $\gamma_s$ are assumed to be equal.

This may be justified by the small contact angle of only about 9.3° by considering the Wulff plot of the surface free energy with respect to the surface orientation.\textsuperscript{16}

In summary, we have experimentally demonstrated the shape transition of coherent 3D islands in the (In,Ga)As/GaAs(100) material system. A series of 1.8-nm-thick (In,Ga)As single layers were grown on GaAs(100) at different temperatures. The surface morphology of the samples was characterized by atomic force microscopy and reflection high-energy electron diffraction. The shape of the coherent 3D islands transforms from round to elongated when increasing the growth temperature. This shape transition is understood by the theoretical work of Tersoff and Tromp. A quantitative agreement is obtained between the theory and our experimental results.

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\begin{figure}
\centering
\includegraphics[width=\textwidth]{fig4.png}
\caption{The solid line shows the width and length of the island as a function of the area calculated numerically according to Eq. (1). The closed circles are the experimental data points corresponding to Figs. 1(a)–1(c). $a_0 = 280 \text{ Å}$.}
\end{figure}

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